ASU NanoFab

https://engineering.asu.edu/nanofab/

https://engineering.asu.edu/nanofab/project/plasma-etching/

Plasma Tools and Materials

Oxford PlasmaLab RIE80+ (F-based)
- Si, SiO2, Si3N4, fused silica/quartz (8" wafer capable)

Oxford PlasmaLab RIE80+ (Cl-based)
- Ru, Al, GeSn, III-Vs (8" wafer capable)

SPTS ICP ASE (Bosch process)
- Si and SiC (4" wafer capable)

SPTS ICP AGE (All General Etch)
- GaN, GaAs, InP, GaInP, AlGaAs (4" wafer capable)

Xactix XeF2 (isotropic)
- Si

Plasmatherm 790 (F-based general etch)
- Si, SiO2, Si3N4, Ru, Ni, Nb, polyimide, BARC (8" wafer capable)

Plasmatherm APEX SLR ICP (Cl- based)
- same as SPTS ICP AGE (8" wafer capable)